

Announcements

- Labs start tomorrow (Experiment 0).
 - Read lab beforehand
 - Each lab group will get a 331 Lab Kit
 - Bring probes, breadboard, components from 233
(will need to buy if lab group doesn't have enough)
- We finish Chapter 2 material today. Start reading Chapter 3.

Drift Diffusion Equations

$$\nabla \cdot \mathbf{E} = \frac{\rho(x)}{\varepsilon} \Rightarrow \frac{dE}{dx} = \frac{\rho(x)}{\varepsilon} \text{ for 1D}$$

$$\nabla^2 \varphi = -\frac{\rho(x)}{\varepsilon} \Rightarrow \frac{d^2 \varphi}{dx^2} = -\frac{\rho(x)}{\varepsilon}$$

$$\mathbf{j}_n^{\text{tot}} = qn\mu_n \mathbf{E} + qD_n \nabla n \Rightarrow qn\mu_n E + qD_n \frac{dn}{dx}$$

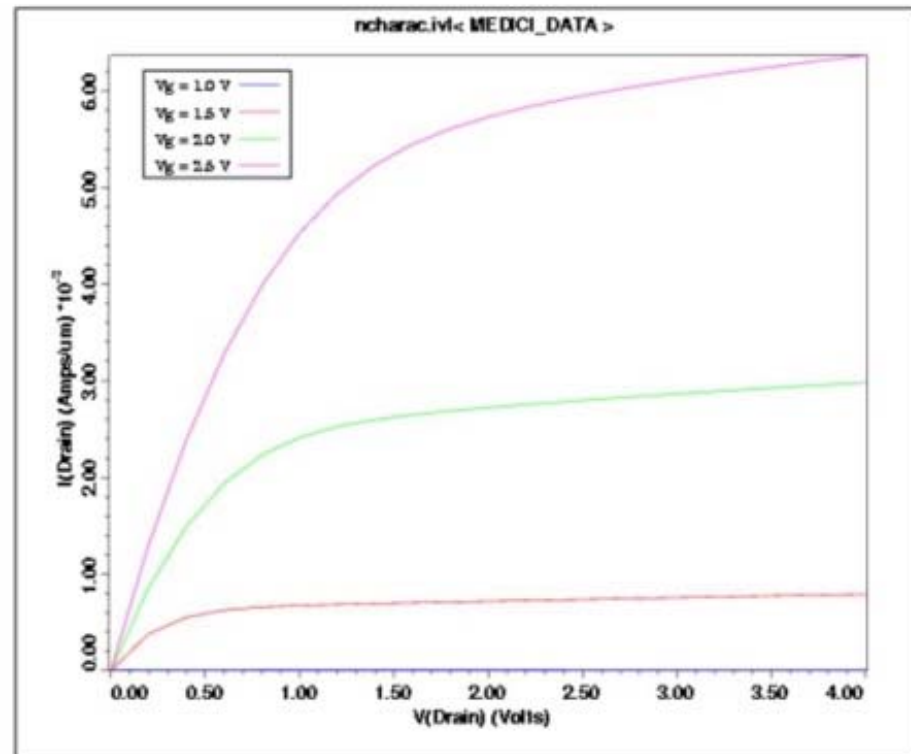
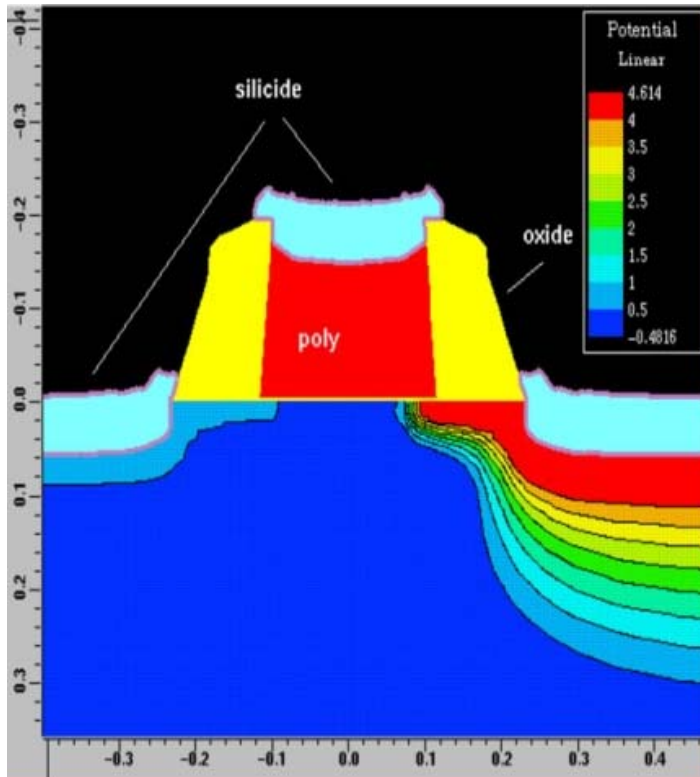
$$\mathbf{j}_p^{\text{tot}} = qp\mu_p \mathbf{E} - qD_p \nabla p \Rightarrow qp\mu_p E - qD_p \frac{dp}{dx}$$

$$\frac{\partial n}{\partial t} = -\nabla \cdot \mathbf{j}_n^{\text{tot}} - R + G \quad (G \text{ is generation})$$

$$\frac{\partial p}{\partial t} = -\nabla \cdot \mathbf{j}_p^{\text{tot}} - R + G \quad (R \text{ is recombination})$$

Device Analysis and Modeling

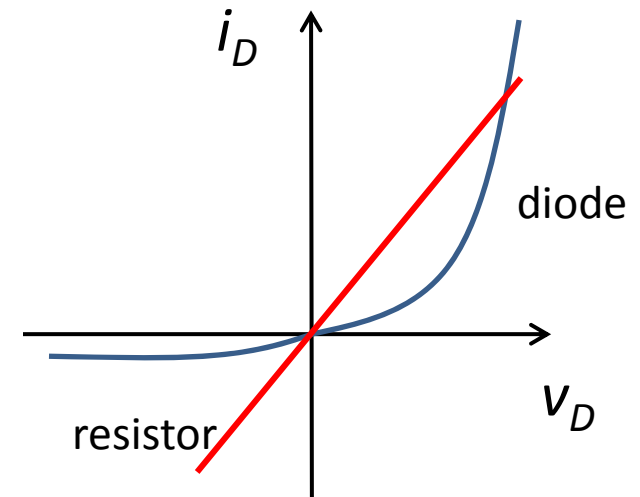
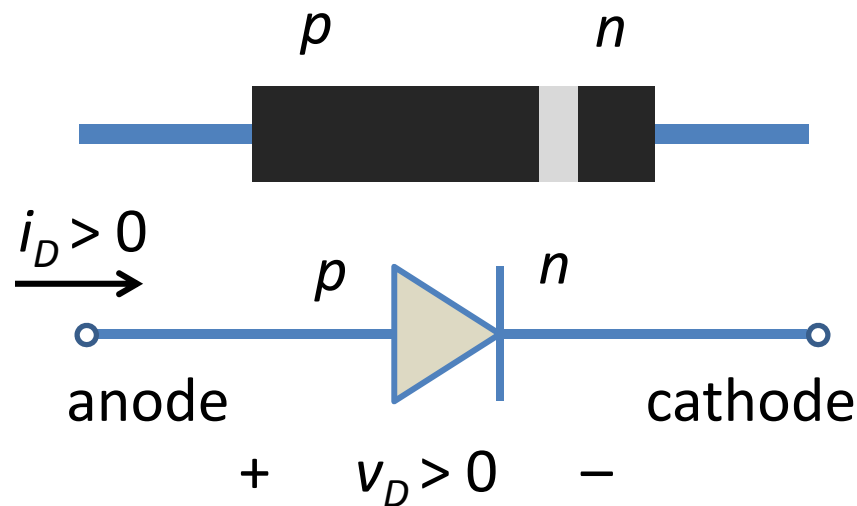
- The drift-diffusion equations are the basis for most analysis and design of semiconductor devices.



EE 331 Devices and Circuits I

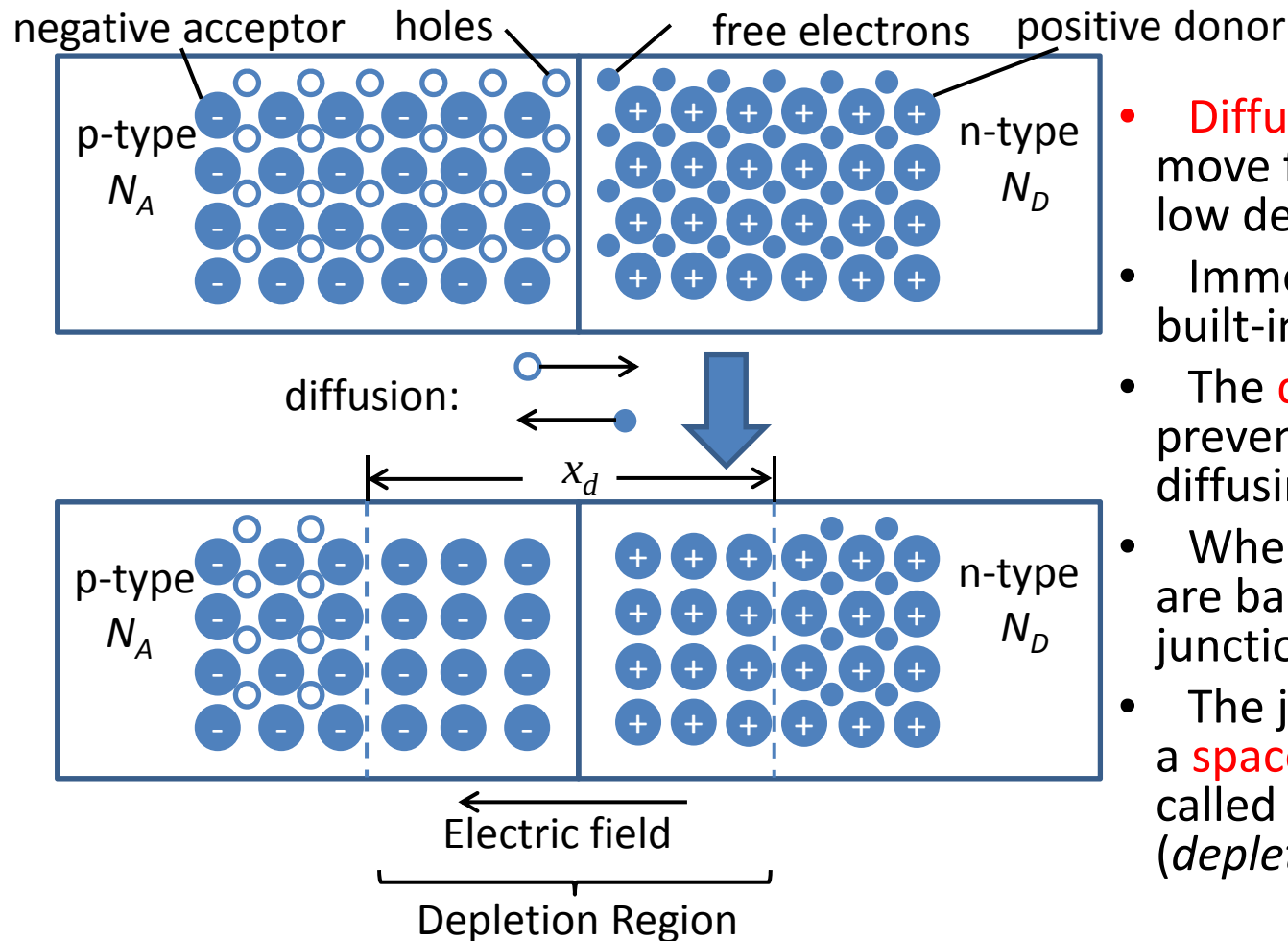
Chapter 3 Diodes – Physics & Characterization

P-N Junction Diodes



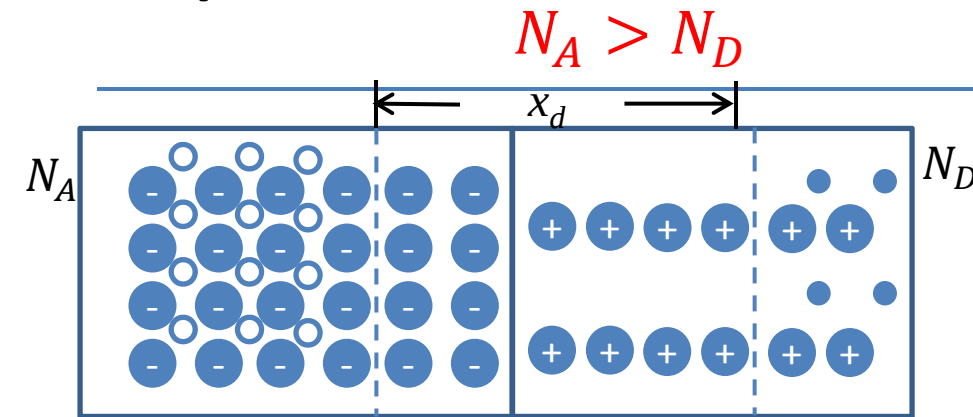
- $v_D > 0$, **forward** bias, $i_D > 0$, large (good forward conduction)
- $v_D < 0$, **reverse** bias, $i_D < 0$, small (poor reverse conduction)
- Goal: Find function of i_D with respect to v_D .

p-n junction – Physical Picture



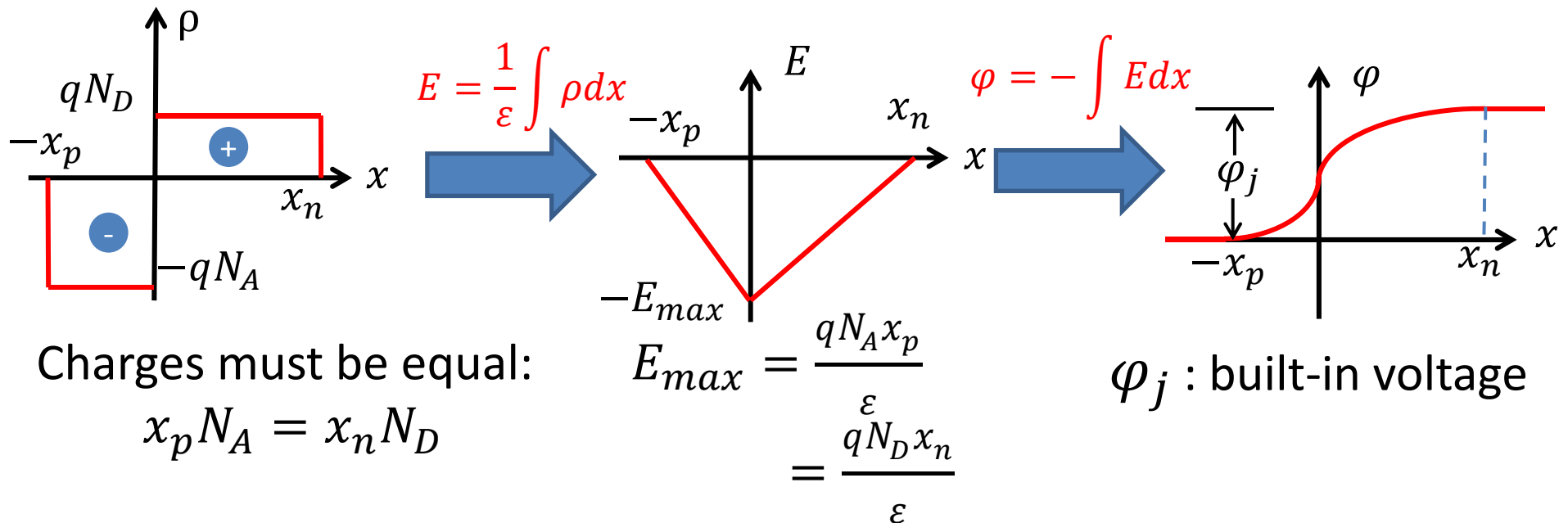
- **Diffusion** allows carriers to move from high density to low density
- Immobile ions produce a built-in electric field
- The **drift** caused by the field prevents the carriers from diffusing further.
- When drift and diffusion are balanced, a metallurgical junction forms
- The junction is featured by a **space charge region**, also called **depletion region** (*depleted* of free carriers).

p-n Junction – Electrostatic Analysis

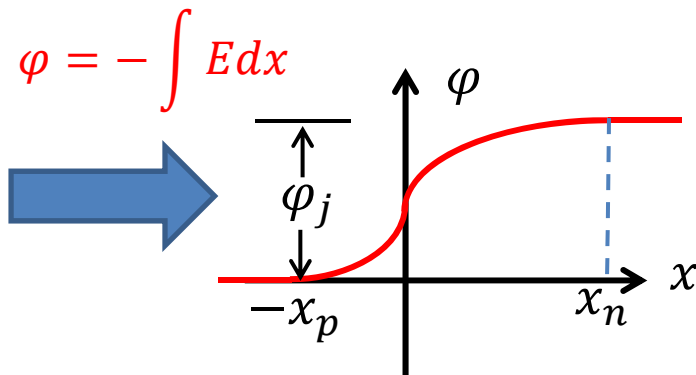
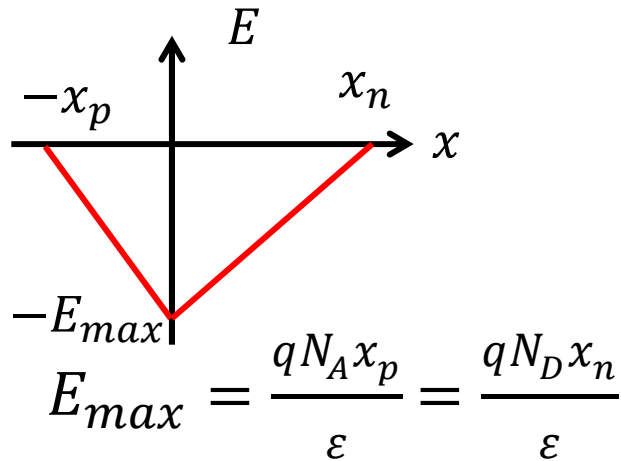


1D Poisson's Equation:

$$\frac{d^2 \phi}{dx^2} = -\frac{dE}{dx} = -\frac{\rho}{\epsilon}$$



p-n Junction – Electrostatic Analysis



- ϕ_j is the area under E - x curve:
- $\phi_j = \frac{(x_n + x_p)}{2} |E_{max}| = \frac{qN_A(x_n + x_p)}{2\epsilon} x_p$
- Combining $x_p N_A = x_n N_D$, we get

$$x_p = \sqrt{\frac{2\epsilon\phi_j}{qN_A(1+N_A/N_D)}}$$

$$x_n = \sqrt{\frac{2\epsilon\phi_j}{qN_D(1+N_D/N_A)}}$$

$$x_d = x_n + x_p = \sqrt{\frac{2\epsilon\phi_j}{q} \left(\frac{1}{N_D} + \frac{1}{N_A} \right)}$$

Depletion width under zero bias

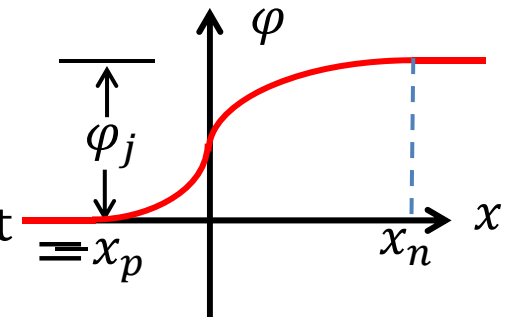
p-n Junction – Electrostatic Analysis

- How to find φ_j ?

- From detailed balance in equilibrium ($J^{\text{drift}} - J^{\text{diff}}$):

$$\varphi_j = \frac{kT}{q} \ln \frac{p_0(-x_p)}{p_0(x_n)} = \frac{kT}{q} \ln \frac{n_0(x_n)}{n_0(-x_p)} = \frac{kT}{q} \ln \frac{N_A N_D}{n_i^2}$$

- φ_j depends on
 - Doping concentration on both sides (N_A, N_D)
 - Temperature (kT)
 - Material ($n_i^2 \sim \exp[-E_g/kT]$)

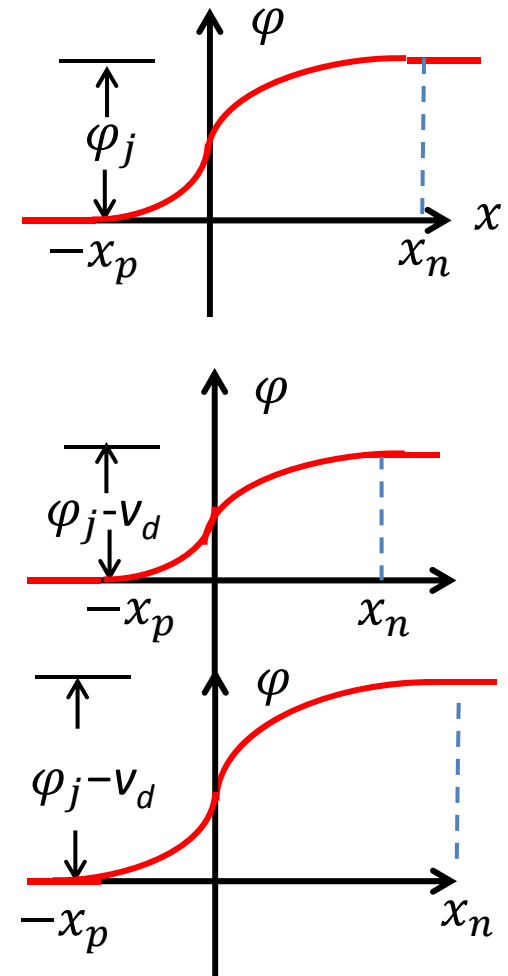


p-n Junction – Applied Voltage

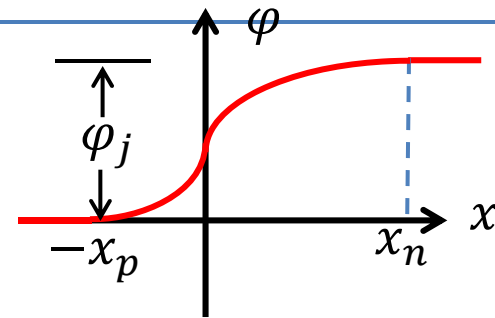
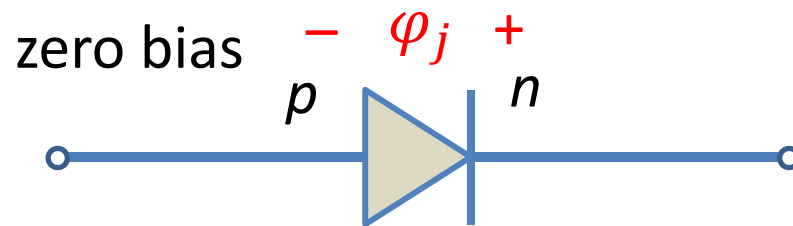
- Applied voltage dropped across x_d .
- Detailed balance still nearly true for $v_d < \varphi_j - 0.1 \text{ V}$ ($J^{\text{drift}} \cong -J^{\text{diff}}$):

$$\varphi_j - v_d = \frac{kT}{q} \ln \frac{p(-x_p)}{p(x_n)} = \frac{kT}{q} \ln \frac{n(x_n)}{n(-x_p)}$$

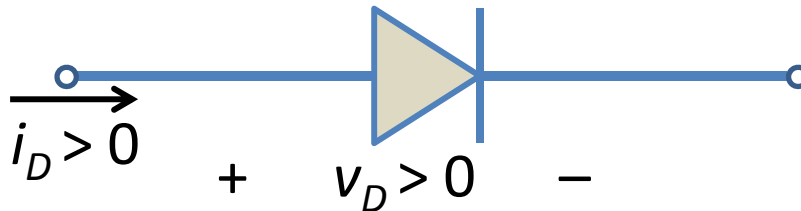
- Forward bias: smaller barrier, narrower depletion region, lower E_{max} .
- Reverse bias: larger barrier, wider depletion region, higher E_{max} .



p-n Junction Under Applied Voltage



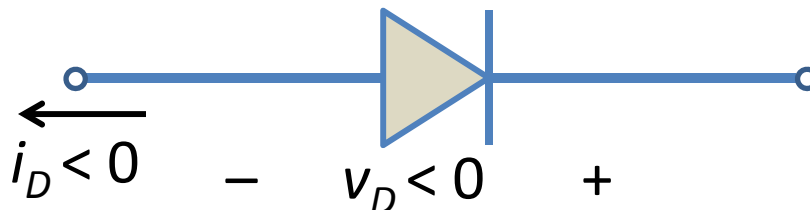
forward bias



- Under bias v_D , replace φ_j with $(\varphi_j - v_D)$. e.g.

$$x_d = \sqrt{\frac{2\varepsilon(\varphi_j - v_D)}{q} \left(\frac{1}{N_D} + \frac{1}{N_A} \right)}$$

reverse bias



- Forward bias, $v_D > 0$, x_d shrinks
- Reverse bias, $v_D < 0$, x_d widens